

Application No. 09/449,907
Attorney Docket No. 107176-09004

the workpiece for polishing the same and disposed in a first plane;

polishing agent passages, having bottoms disposed in a second plane, for
introducing a polishing agent; and

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concl
a plurality of one-stage step portions formed between said polishing faces of said
polishing projections and the bottoms of said polishing agent passages and disposed in
a third plane, the first, second and third planes spaced apart from and extending
parallel to one another.

5A. (Once Amended) A chemical mechanical polishing apparatus,
comprising:

a chemical mechanical polishing cloth for chemically mechanically polishing a
workpiece;

a polishing head for holding and rubbing a workpiece with said chemical
mechanical polishing cloth; and

a polishing agent supply mechanism for supplying a polishing agent to said
chemical mechanical polishing cloth,

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said chemical mechanical polishing cloth including, on an opposite-to-
workpiece face thereof:

polishing projections having polishing faces arranged to come in contact with
the workpiece for polishing the same and disposed in a first plane;

polishing agent passages, having bottoms disposed in a second plane, for
introducing a polishing agent; and

a plurality of one-stage step portions formed between said polishing faces of
said polishing projections and the bottoms of said polishing agent passages and